
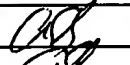



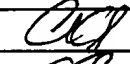
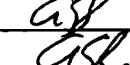
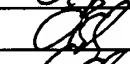

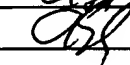





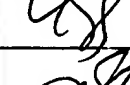
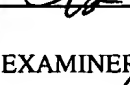




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			APPLICANT Badri N. KRISHNAMURTHY et al.			
			FILING DATE August 14, 2001		GROUP 2171	

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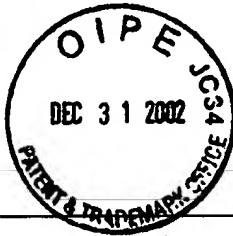
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						Yes	No
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	WO 98/45090	10/15/98	WO			X	
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